Supporting Information

Efficient selective hydrogenation of phenylacetylene over intermetallic Ni-Sb catalyst

Yao Fan,^a Chenyang Lu,^{*a} Aonan Zeng,^b Yinjie Deng,^c Ling Qin,^c Shihong Zhou,^a Mengxin Wang,^a Anjie Wang,^b Luxi Tan,^{*a} Lichun Dong^{*a}

Experimental Section

Preparation of Ni/SiO₂ and Ni_xSb_y/SiO₂

Firstly, stoichiometric NiCl₂ and/or SbCl₃ were dissolved in the hydrochloric acid solution to make a mixed salt solution. The resulting mixture was added dropwise into the SiO₂ support under continuous stirring, followed by aging for 24 hours to afford the chloride precursor. The precursor was then reduced at 800 °C in H₂ for 1 h. After cooling to room temperature, the resulting product was ground into a fine powder using an agate mortar, yielding SiO₂-supported Ni_xSb_y intermetallic compounds and monometallic Ni catalysts.

Preparation of Sb/SiO₂ and Sb/SiO₂-H

An appropriate amount of antimony powder was thoroughly mixed with SiO₂ powder. The mixture was then placed into a ball-milling jar with agate beads of varying sizes, followed by mechanical ball milling at 600 rpm for 1 h, denoted as Sb/SiO₂. Then the Sb/SiO₂ sample by mixing Sb and SiO₂ was treated in H₂ at 800 °C for 1 h, which is following the same method for preparing Ni_xSb_y/SiO₂ (denoted as Sb/SiO₂-H).

Characterization

The powder X-ray diffraction (XRD) measurement was conducted on a PANalytical X-ray diffractometer with Cu K α radiation (40 kV, 100 mA). The scanning ranged from 10° to 80° with a scanning speed of 8 °/min. Transmission electron microscopy (TEM), high-resolution transmission electron microscopy (HRTEM) and energy-dispersive X-ray spectroscopy (EDS) elemental mapping images were obtained on a Talos F200S microscope. X-ray photoelectron spectroscopy (XPS) measurement was performed on a Scientific K-Alpha spectrometer equipped with a monochromatic Al K α excitation source (hv = 1486.6 eV). All binding energies were calibrated with reference to the C 1 s peak (284.8 eV). Ni contents in different materials were quantified using inductively coupled plasma optical emission spectrometry (ICP-AES, Agilent 5110). Hydrogen temperature-programmed desorption (H₂-TPD) measurements were conducted using a GC (FULI 9790II) analyzer with a thermal conductivity detector (TCD). In a typical process, the sample (50 mg) was loaded into a U-shaped quartz tube, pretreated under a H₂ and Ar mixture (1:9, v/v) at 400 °C for 1 h. Subsequently, the reduced sample was

purged in Ar at 400 °C for 30 min, then cooled down to room temperatur. After H₂ adsorption saturation, the system was flushed with Ar for 30 min. Finally, the temperature was increased to 500 °C at a heating rate of 10 °C min⁻¹ under Ar flow, and the desorption profiles were recorded. Nitrogen adsorption-desorption isotherms were measured at -196 °C on a Micromeritics Tristar II 3020 instrument. The specific surface area was calculated according to the Brumauer–Emmett–Teller method, while the pore volume and average pore size were calculated from the desorption branch of the N₂ adsorption–desorption isotherm by the Barrett–Joyner–Halenda method.

Catalytic Performance

Semi-hydrogenation of phenylacetylene was conducted in a 100 mL micro mechanical stirred reactor. Initially, ethanol (20 mL), phenylacetylene (2 mmol), and the catalyst (100 mg) were loaded into the reactor. Subsequently, purge with H₂ ten times to remove air from the reactor. The reaction proceeded under 2 MPa H₂ pressure with programmed temperature control and stirring at 200 rpm for 2 h. The liquid-phase composition was analyzed offline using gas chromatography (Nexis GC-2030) to track changes with temperature. The phenylacetylene conversion and product selectivity were calculated as follows.

$$C_8 H_6 \text{ conversion} = \frac{c_0 - c_0'}{c_0} \times 100\%$$
 (1)

$$C_8 H_8 \text{ selectivity} = \frac{c_1}{c_1 + c_2} \times 100\% \tag{2}$$

$$C_8 H_{10} \text{ selectivity} = \frac{c_2}{c_1 + c_2} \times 100\% \tag{3}$$

where c_0 and c_0' represent the concentrations of phenylacetylene before and after the reaction, respectively, while c_1 and c_2 denote the concentrations of styrene and ethylbenzene in the product, respectively.

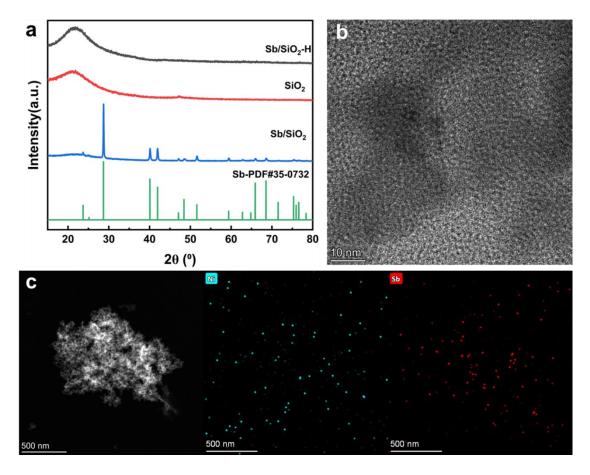


Fig. S1 (a) XRD pattern, (b) HRTEM and (c) EDS-mapping images of Sb/SiO₂-H.

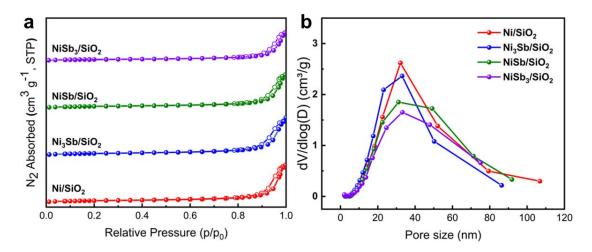


Fig. S2 (a) N_2 adsorption-desorption isotherms and (b) pore size distribution of the Ni_xSb_y/SiO_2 catalysts.

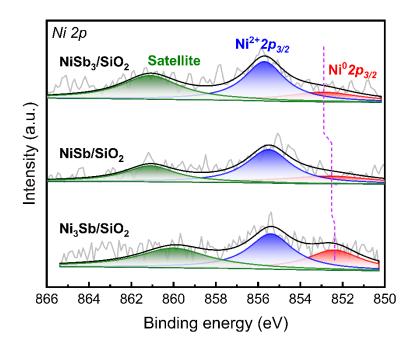


Fig. S3 Ni 2p XPS spectra of the NiSb₃/SiO₂, NiSb/SiO₂ and Ni₃Sb/SiO₂ catalysts.

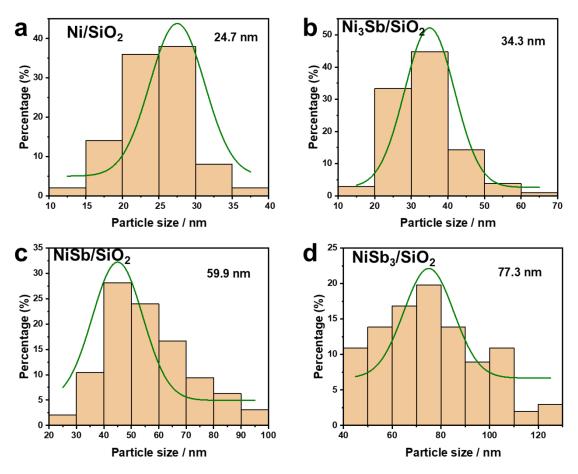


Fig. S4. Particle size distribution of (a) Ni/SiO₂, (b) Ni₃Sb/SiO₂, (c) NiSb/SiO₂ and (d) NiSb₃/SiO₂.

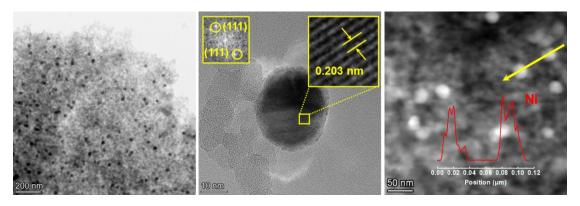


Fig. S5 HRTEM images, associated FFT pattern and EDS line-scanning profile for the Ni/SiO₂ catalyst.

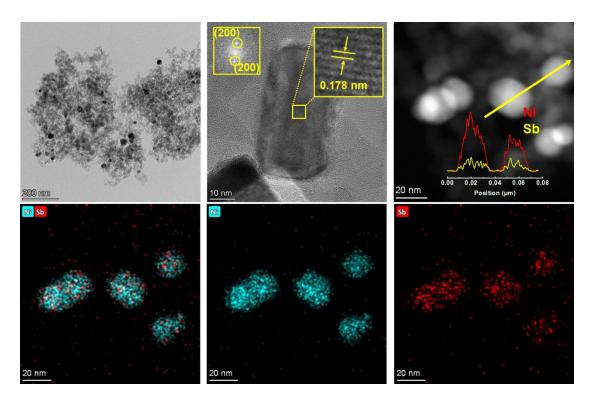


Fig. S6 HRTEM images, associated FFT pattern, EDS mapping images and line-scanning profile for the Ni₃Sb/SiO₂ catalyst.

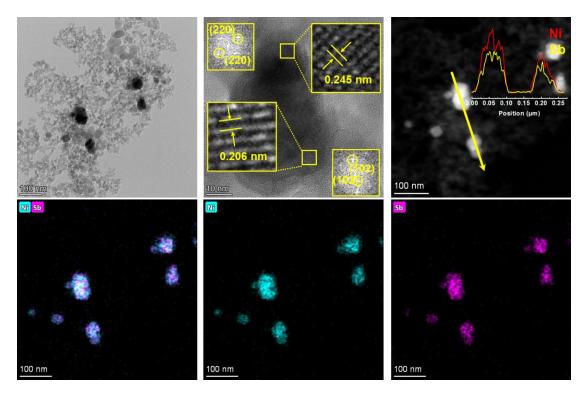


Fig. S7 HRTEM images, associated FFT pattern, EDS mapping images and line-scanning profile for the NiSb/SiO₂ catalyst.

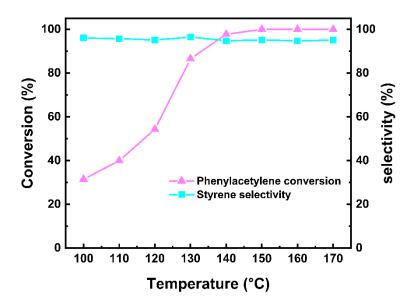


Fig. S8 Phenylacetylene conversion and styrene selectivity as a function of reaction temperature over $NiSb_3/SiO_2$.

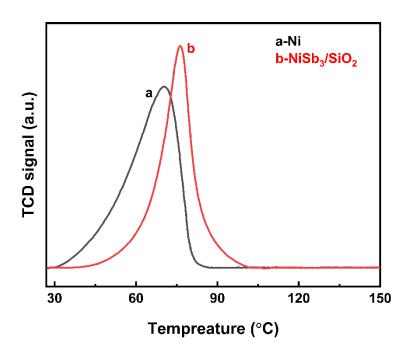


Fig. S9 H₂-TPD profiles of Ni/SiO₂ and NiSb₃/SiO₂.

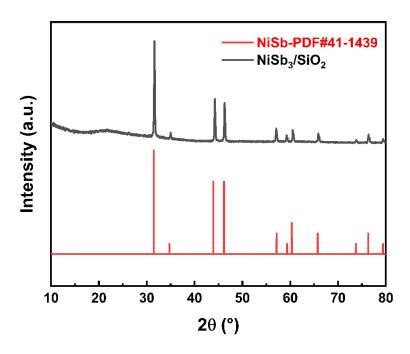


Fig. S10 XRD pattern of the spent NiSb₃/SiO₂ catalyst after ten reactions.

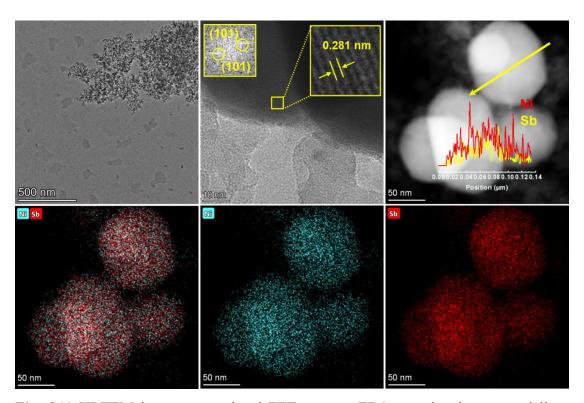


Fig. S11 HRTEM images, associated FFT pattern, EDS mapping images and line-scanning profile for the spent NiSb₃/SiO₂ catalyst.

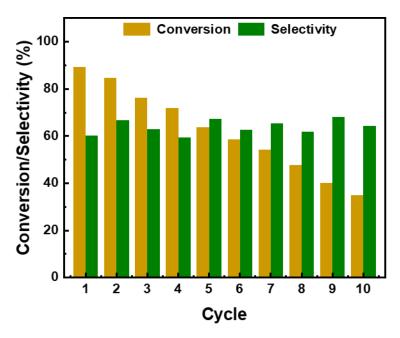


Fig. S12 Stability test of Ni/SiO₂.

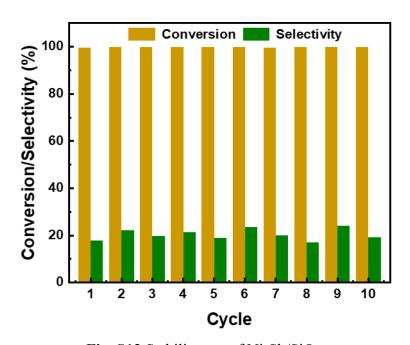


Fig. S13 Stability test of Ni₃Sb/SiO₂.

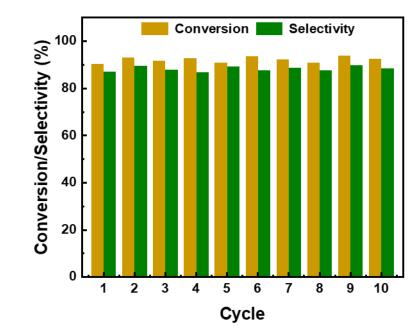


Fig. S14 Stability test of $NiSb/SiO_2$.

Table S1 The Ni loading of the supported Ni-based catalysts determined by ICP-AES

Catalysts	Ni/SiO ₂	Ni ₃ Sb/SiO ₂	NiSb/SiO ₂	NiSb ₃ /SiO ₂
Ni mass fraction (wt.%)	4.770	4.916	5.006	5.941
Sb mass fraction (wt.%)	_	2.0076	5.892	12.325
molar ratio (Ni/Sb)	_	5.080	1.763	1.000

Table S2 BET surface area and average pore diameter of different catalysts.

Catalysts	Ni/SiO ₂	Ni ₃ Sb/SiO ₂	NiSb/SiO ₂	NiSb ₃ /SiO ₂
Surface area (m ² /g)	199.8	205.1	186.3	157.5
Average pore diameter (nm)	28.1	25.1	28.0	26.4

Table S3 Comparison of catalytic performance of different catalysts for the semi-hydrogenation reaction of phenylacetylene.

Catalysts	T (°C)	Conv. (%)	Sel. (%)	Ref.	
NiSb ₃ /SiO ₂	150	100	95.2	This Work	
Ni-rich AlNi ₃	50	99	88	1	
$NiZn_3/\alpha\text{-}Al_2O_3$	60	> 99	92	2	
Ni ₃ CuSn/SiO ₂	60	99.2	94.6	3	
Ni@NC-800	110	97	94	4	
fcc Ag@hcp Ni	70	100	95.1	5	
Ni ₁ +Ni ₂ P _n @PBNC	60	100	96.2	6	
PdIn-QT	25	96	93	7	
Pd ₁ /Ni@G	30	100	93	8	
Pd_1Ag_5/g - C_3N_4	25	98	> 93	9	
UiO-67@Pd@UiO-67	10	100	93.1	10	
Pd ₁ /NC-PHF	60	93.1	93.5	11	
$Pd_1/ZIF-8$	120	100	93.6	12	
$Pd_{0.5}/Ni_{0.5}@\gamma$ - Al_2O_3	25	98	94	13	
Pd ₆ /TiO ₂	50	94.9	94	14	
Pd_1/G	25	100	94	15	
PPh ₃ -Pd/Al ₂ O ₃ -9	25	99	95	16	
h-Pd-Mn/NC	60	99	95	17	
Pd-Pb NSs	40	100	95.8	18	
CuPd@ZIF-8	25	97	96	19	
Pd ₁ @ZSM-5	65	100	95	20	
Pd ₁ +Pd _n @NC/HAP	30	93.8	96.1	21	

Table S4. Phenylacetylene conversion and styrene selectivity as a function of reaction temperature over NiSb₃/SiO₂.

Catalysts	Temperature (°C)	Time (h)	Conv. (%)	Sel. (%)
NiSb ₃ /SiO ₂	150	2	100	94.4
NiSb ₃ /SiO ₂	150	3	100	95.8
NiSb ₃ /SiO ₂	150	4	100	94.9

Table S5. Hydrogenation of various alkynes over the NiSb₃/SiO₂ catalyst.

	R ¹	−R² −	H ₂	- /==	R ²	
Entry	Substrates	T (°C)	P (MPa)	Time (h)	Conv. (%)	Sel. (%)
1	Н ₃ С	140	1.0	2	96.7	92.3
2	СН ₃	80	0.5	2	93.1	90.5
3	OCH ₃	110	1.0	2	98.5	91.1
4	F	100	1.0	2	99.9	90.7
5	cı	100	1.0	2	99.9	90.2
6	NH ₂	110	1.0	2	94.6	91.4
7	$HC \equiv C(CH_2)_3CH_3$	150	1.0	2	94.5	88.5

Reaction conditions: substrate 2 mmol, ethanol 20 mL, catalyst 100 mg.

References

- 1 H. Liu, X. Chen, S. Liu, Y. Du, W. Zhu, Z. Hu, M. Armbrüster and C. Liang, *Ind. Eng. Chem. Res.*, 2024, **63**, 3608-3620.
- 2 Z. Bao, L. Yang, Z. Cheng and Z. Zhou, *Ind. Eng. Chem. Res.*, 2020, **59**, 4322-4332.
- 3 W. Chen, H. Xu, X. Ma, L. Qi and Z. Zhou, Chem. Eng. J., 2023, 455, 140565.
- 4 X. Wang, T. Song, G. Fu and Y. Yang, ACS Catal., 2023, 13, 11634-11643.
- 5 J. Su, Y. Ji, S. Geng, L. Li, D. Liu, H. Yu, B. Song, Y. Li, C. W. Pao, Z. Hu, X. Huang, J. Lu and Q. Shao, Adv. Mater., 2024, 36, 2308839.
- 6. Z. Chen, Y. Chen, L. Shi, X. Li, G. Xu, X. Zeng, X. Zheng, Z. Qi, K. Zhang, J. Li, S. Zhang, Z. Zhao and Y. Zhang, *Adv. Mater.*, 2024, **36**, 2405733.
- 7 J. S. Martinez, J. Mazarío, C. W. Lopes, S. Trasobares, J. J. Calvino Gamez, G. Agostini and P. Oña-Burgos, *ACS Catal.*, 2024, **14**, 4768-4785.
- 8 L. Zhao, X. Qin, X. Zhang, X. Cai, F. Huang, Z. Jia, J. Diao, D. Xiao, Z. Jiang, R. Lu, N. Wang, H. Liu and D. Ma, *Adv. Mater.*, 2022, **34**, 2110455.
- 9 X. Guo, C. Feng, Z. Yang, S. Hasegawa, K. Motokura and Y. Yang, *ACS Nano*, 2025, **19**, 2788-2798.
- 10 K. Choe, F. Zheng, H. Wang, Y. Yuan, W. Zhao, G. Xue, X. Qiu, M. Ri, X. Shi, Y. Wang, G. Li and Z. Tang, *Angew. Chem., Int. Ed.*, 2020, **59**, 3650-3657.
- 11 S. Li, G. Yue, H. Li, J. Liu, L. Hou, N. Wang, C. Cao, Z. Cui and Y. Zhao, *Chem. Eng. J.*, 2023, **454**, 140031.
- 12 X. Li, F. Zhang, X. Han, J. H. Wang, X. Cui, P. Xing, H. Li and X. M. Zhang, *Nano Res.*, 2023, 16, 8003-8011.
- 13 X. Song, F. Shao, Z. Zhao, X. Li, Z. Wei and J. Wang, ACS Catal., 2022, 12, 14846-14855.
- 14 J. Tang, K. Jia, R. Zhang, C. Liu, X. Lin, T. Ge, X. Liu, Q. Zhao, W. Liu, D. Ma, H. Fan and J. Huang, *ACS Catal.*, 2024, **14**, 2463-2472.
- 15 K. Zhang, H. L. Cheng, Y. Wang, Y. Liu, Z. W. Xing, P. Tan, Y. Nian, Y. Han and L. B. Sun, AIChE J., 2025, 71, e18897.
- 16 M. Wang, Y. Chen, X. Liu, Z. Zhao, L. Ren, S. Huang, G. Dong, M. Xia, X. Li, Z. Wei and J. Wang, AIChE J., 2024, 70, e18386.
- 17 H. Liu, P. Zhu, D. Yang, C. Zhong, J. Li, X. Liang, L. Wang, H. Yin, D. Wang and Y. Li, *J. Am. Chem. Soc.*, 2024, **146**, 2132-2140.
- 18 C. Shen, Y. Ji, P. Wang, S. Bai, M. Wang, Y. Li, X. Huang and Q. Shao, *ACS Catal.*, 2021, **11**, 5231-5239.
- 19 L. Li, W. Yang, Q. Yang, Q. Guan, J. Lu, S. H. Yu and H. L. Jiang, ACS Catal., 2020, 10, 7753-7762.
- 20 H. Liu, J. Li, X. Liang, H. Ren, H. Yin, L. Wang, D. Yang, D. Wang and Y. Li, *J. Am. Chem. Soc.*, 2024, **146**, 24033-24041.
- 21 Z. Chen, C. Wang, B. Zhang, J. Li, D. Wang, G. Xu, J. Zhang, M. Peng, D. Ma and Y. Zhang, Adv. Mater., 2025, 37, 2503841.